



# 제 32회 한국반도체학술대회

The 32nd Korean Conference on Semiconductors

2025년 2월 12일(수)-14일(금) | 강원도 하이원리조트

## Future Normal in Semiconductor

2025년 2월 13일(목), 09:00-10:45

Room F(사파이어 I), 5층

### C. Material Growth & Characterization 분과

#### 006\_[TF1-C] Complex Oxide Thin Films and Heterostructures

좌장: 김태현 책임박사(KIST), 이수길 교수(가천대학교)

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| 초청<br>TF1-C-1<br>09:00-09:30 | <b>Superconducting Epitaxial Thin Films of (111) KTaO<sub>3</sub> Grown by Hybrid PLD</b><br>Jieun Kim<br>Department of Materials Science and Engineering, KAIST                                                                                                                                                                                                                                                                                                                       |
| TF1-C-2<br>09:30-09:45       | <b>Thermal Characterization of Phase-Separated TiO<sub>2</sub> Thin Films Deposited by Plasma-Enhanced Atomic Layer Deposition</b><br>Jihyun Kim <sup>1</sup> , Seunghyeon Lee <sup>2</sup> , Sung Il Park <sup>1</sup> , Jongwon Baek <sup>1</sup> , Dongyun Seo <sup>1</sup> , Gyung-Min Choi, Jihwan An <sup>3</sup> , and Jungwan Cho <sup>1</sup><br><sup>1</sup> Sungkyunkwan University, <sup>2</sup> Seoul National University of Science and Technology, <sup>3</sup> POSTECH |
| TF1-C-3<br>09:45-10:00       | <b>MOCVD 성장 변수에 따른 Ga<sub>2</sub>O<sub>3</sub> 박막의 상전이 거동 분석과 단일상 성장 연구</b><br>김형윤 <sup>1,2</sup> , 김선재 <sup>1,3</sup> , 신재명 <sup>1</sup> , 이도원 <sup>1</sup> , 박지현 <sup>1</sup> , 전대우 <sup>1</sup><br><sup>1</sup> 한국세라믹기술원, <sup>2</sup> 고려대학교, <sup>3</sup> 한국항공대학교                                                                                                                                                                                                                  |
| 초청<br>TF1-C-4<br>10:00-10:30 | <b>Topotactic Engineering for Oxide Quantum Materials</b><br>Woo Jin Kim<br>School of Materials Science and Engineering, Pusan National University                                                                                                                                                                                                                                                                                                                                     |
| TF1-C-5<br>10:30-10:45       | <b>Graphene/Oxide Hybrid Heterostructures</b><br>Woo Seok Choi<br>Department of Physics, Sungkyunkwan University                                                                                                                                                                                                                                                                                                                                                                       |